

SUBSTRATE PROCESSING APPARATUS, SUBSTRATE PROCESSING METHOD,
AND STORAGE MEDIUM THAT STORES PROGRAM TO CAUSE COMPUTER IN
SUBSTRATE PROCESSING APPARATUS TO EXECUTE SUBSTRATE PROCESSING
METHOD

ABSTRACT

Accuracy of detection of a fly out of a substrate from a polishing head is improved. A substrate processing apparatus includes a polishing table 350 to which a polishing pad 352 for polishing the substrate is attachable, a polishing head 302 for holding and pressing the substrate against the polishing pad 352, a retainer member disposed surrounding the polishing head 302, a retainer member pressurization chamber disposed adjacent to the retainer member, an arm 360 for holding and turning the polishing head 302, and a slip out detector 910 for detecting a fly out of the substrate from the polishing head 302 based on a turning torque of the arm 360 or based on a flow rate of a fluid supplied to the retainer member pressurization chamber.

Selected Drawing: Fig. 2